

AMENDMENTS TO THE CLAIMS:

Please cancel Claims 1 through 14 without prejudice or disclaimer of subject matter.

Please add claims 15 through 29 as follows:

1-14. (Cancelled)

15. (New) An exposure apparatus which has a projection optical system and transfers a pattern of a mask to a substrate via said projection optical system, said apparatus comprising:

a base;

a first structure;

a first vibration isolating mechanism which is arranged on said base and supports said first structure;

a first partition wall which defines a first space including an optical path of said projection optical system;

a first elastic seal member which couples said first structure and said first partition wall, and seals the first space; and

a first support member which is arranged on said base and is different from said first vibration isolating mechanism, and supports said first partition wall.

16. (New) an apparatus according to Claim 15, further comprising:

a second structure;

a second vibration isolating mechanism which is arranged on said base and is different from said first vibration isolating mechanism, and supports said second structure; and

a second elastic seal member which couples said second structure and said first partition wall and seals the first space.

17. (New) An apparatus according to Claim 15, further comprising a substrate stage to hold the substrate and move, and a mask stage to hold the mask and move,

wherein at least one of said substrate stage and said mask stage is arranged in the first space.

18. (New) An apparatus according to Claim 15, further comprising a gas supply system which supplies a gas into the first space.

19. (New) An apparatus according to Claim 18, wherein the gas supplied by said gas supply system includes one of clean dry air and an inert gas.

20. (New) An apparatus according to Claim 18, further comprising another elastic seal member which couples a supply port of said gas supply system and said first partition wall.

21. (New) An apparatus according to Claim 15, wherein said partition wall comprises one of a door and a lid.

22. (New) An apparatus according to Claim 15, further comprising a second partition wall which defines a second space different from the first space and another elastic seal member which couples said first and second partition walls.

23. (New) An apparatus according to Claim 16, further comprising a second partition wall which defines a second space different from the first space and another elastic seal member which couples said first and second partition walls.

24. (New) An apparatus according to Claim 23, further comprising:  
a third structure which is different from said first and second structures; and  
a second support member which is different from said first support member and said first vibration isolating mechanism, and supports said third structure,  
wherein said second partition wall is arranged on said third structure.

25. (New) An apparatus according to Claim 22, further comprising at least one of a substrate transfer system which transfers the substrate and a mask transfer system which transfers the mask, wherein at least one of said substrate transfer system and said mask transfer system is arranged in the second space.

26. (New) An apparatus according to Claim 17, further comprising:  
a reaction force receiving structure which receives a reaction force from one of said substrate stage and said mask stage via a through-hole formed in said first partition wall; and

an elastic seal member which seal the through-hole via which said reaction force receiving structure is arranged.

27. (New) An apparatus according to Claim 15, wherein said first elastic seal member has a structure of a bellows.

28. An apparatus according to Claim 27, wherein said first elastic seal member is formed from one of a metal film, a resin, and a composite material of the metal film and the resin.

29. (New) A device manufacturing method comprising the steps of:  
transferring a pattern of a mask to a substrate using an exposure apparatus as recited in Claim 15; and  
developing the substrate to which the pattern has been transferred.